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APPLICANT : CENTRAL GLASS CO LTD;

INVENTOR : NAKAGAWA SHINSUKE;

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TITLE : GAS FOR PLASMA CVM

ABSTRACT : PURPOSE: To solve the problems of a low machining speed and low efficiency of utilization of gas of using gas for machining selected from among  $F_2$ , interhalogen compds. and nitrogen fluorides.

CONSTITUTION: This gas for plasma CVM (Chemical Vaporization Machining) is one kind of gas or a mixture of two or more kinds of gases selected from among  $F_2$ , interhalogen compds. and nitrogen fluorides. The interhalogen compds. are  $ClF$ ,  $ClF_3$ ,  $ClF_5$ ,  $BrB$ ,  $BrB_3$ ,  $BrF_5$  and  $BrF_7$ . The nitrogen fluorides are  $NF_3$ ,  $N_2F_4$ ,  $N_2F_2$  and  $N_3F$ . Contamination by the deposition of sulfur or its compd. and carbon or its compd. from the surfaces of a body to be machined and an electrode material can be prevented.

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